



*CCS provides value-added solutions to the customers we serve. Our Sales Team covers the New England States; Massachusetts, Connecticut, New Hampshire, Vermont, Maine, and Rhode Island, as well as New York. While we serve all markets, our major focus includes Medical Device, Converting, Semiconductor, Defense, and Industrial.*



From initial design and engineering to final installation, We provide expertise & service for every aspect of a cleanroom. We work closely with each client to ensure specific requirements are met. In addition, FLOW can supply all the equipment, furnishings, and essential high-quality supplies to create efficient and contaminant free environments



Peak Gas Generation is the global leader & innovator in high performance Hydrogen & Nitrogen gas generators. By installing an on-site nitrogen generator, manufacturing facilities can take full control of their nitrogen process gas supply.



Plastimation has supplied custom EOAT, Robot, Automation Systems and Controls Integration for 10 years. Capabilities Include:

- Epson Authorized Integrator
- Design, Build & Integrate System Control Systems (Allen Bradley, Siemens, Mitsubishi and Beckhoff)



Polymag® Tek manufactures innovative contact web cleaners, sheet cleaners, and process roll cleaners for the coating, laminating, printing and converting industries - custom designed to remove dirt, contamination, slitting dust and converting debris.



Static Clean provides unique Particle Capturing Systems that not only eliminate static electricity, but source captures FM (Foreign Material). It has been long established that particles found in medical trays, pouches and blisters are a major problem that cause rejects, tear-downs and rework. "Static Electricity" is the biggest contributing factor to this problem because electrostatically charged materials become a dirt magnet for airborne particles that include fibers, mold flash, angel hair, eye lashes, skin flakes, etc. SCI Particle Traps and Particle Capturing Systems control the static and source capture particles.